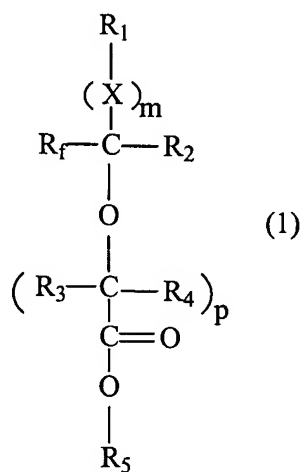


Abstract

The present invention relates to a photoresist composition comprising a photoacid generator and at least one polymer comprising at least one unit as  
 5 described by structure 1,



The invention also relates to a process for imaging the photoresist composition of the present invention, and to a process of making the polymer in  
 10 the presence of an organic base.